

JC09 Rec'd PCT/PTO 17 OCT 2005

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Shuichi OKAWA et al.

Application No.: New U.S. National Stage of
PCT/JP04/008232

Filed: October 17, 2005

Docket No.: 125685

For: MASK MATERIAL FOR REACTIVE ION ETCHING, MASK, AND DRY ETCHING
METHODINFORMATION DISCLOSURE STATEMENTCommissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Relevance of the non-English language references 2, 3, 5 and 6 is discussed in the present specification.
- ☒ 3. References 1-4 were cited in the International Search Report. An English language version of the International Search Report is attached for the Examiner's information.
- ☒ 4. English language Abstracts of the non-English language references 1-6 are attached hereto.


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- ☒ 5. A computer-generated English language translation of the following Japanese Patent Publication has been obtained from the website of the Japanese Patent Office (<http://www.jpo.go.jp>), and is attached, but has not been reviewed for accuracy. See References 1-3, 5 & 6.

Respectfully submitted,


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Date: October 17, 2005

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Sheet 1 of 1

Form PTO-1449
(REV. 8-83)US Dept. of Commerce
PATENT & TRADEMARK OFFICEATTY DOCKET NO.
125685APPLICATION NO.
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PCT/JP04/008232

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

APPLICANTS
Shuichi OKAWA et al.FILING DATE
October 17, 2005

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
	1	JP A 2002-038285 w/abstr. & trans.	02/06/2002	JAPAN		
	2	JP A 2000-322710 w/abstr. & trans.	11/24/2000	JAPAN		
	3	JP A 2001-274144 w/abstr. & trans.	10/05/2001	JAPAN		
	4	JP A 64-36023 w/ abstract	02/07/1989	JAPAN		
	5	JP A 11-92971 w/abstr. & trans.	04/06/1999	JAPAN		
	6	JP A 09-97419 w/ abstr. & trans.	04/08/1997			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

EXAMINER

DATE CONSIDERED

Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Date: October 17, 2005